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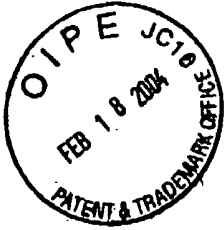
INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

Scott Fuller et al.
Applicants

(Use several sheets if necessary)

January 15, 2004
Filing Date

1756
Group



U. S. PATENT DOCUMENTS

Examiner Initial	Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
<u>NS</u>	4,102,683	07/25/78	DiPiazza	96	38.4	
	4,357,416	11/02/82	Fan	430	302	
	5,234,990	08/10/93	Flaim et al. *	524	609	
	5,278,010	01/11/94	Day et al.	430	18	
	5,554,485	09/10/96	Dichiara et al. *	430	271.1	
	5,723,237	03/03/98	Kobayashi et al. *	430	30	
	5,879,853	03/09/99	Azuma *	430	166	
	5,879,863	03/09/99	Azuma et al.	430	322	
	5,935,768	08/10/99	Biche et al. **	430	401	
	5,939,236	08/17/99	Pavelchek et al.	430	273.1	
	6,048,672	04/11/00	Cameron et al.	430	327	
<u>NS</u>	6,110,638	08/29/00	Masuda et al. **	430	270.1	

Examiner	Date Considered
<u>Michelle Hancock</u>	<u>7/25/04</u>

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

* Cited in a Search Report in corresponding PCT Application No. PCT/US02/22609.

** Cited during the prosecution of the parent application, U.S. Application Serial No. 09/912,116.

U. S. PATENT DOCUMENTS

2/18/04

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Issue Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Filing Date If Appropriate</u>
ws	6,156,479	12/05/00	Meador et al.	430	270.1	
	6,169,029	01/02/01	Yang **	438	671	
	6,183,915	02/06/01	Rolfson **	430	5	
	6,316,167	11/13/01	Angelopoulos et al. **	430	313	01/10/00
	6,340,553	01/22/02	Oomori et al. **	430	270.1	06/02/00
	6,353,209	03/05/02	Schaper et al. **	219	444.1	12/08/99
ms	6,433,348	08/13/02	Abboud et al. **	250	492.2	07/25/00

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<u>Examiner Initial</u>	<u>Document Number</u>	<u>Publication Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Filing Date</u>
ms	2002/0012876 A1	01/31/02	Angelopoulos et al. *	430	271.1	08/17/01
ms	2002/0182514 A1	12/05/02	Montgomery et al. **	430	5	05/03/01

<u>Examiner</u>	<u>Date Considered</u>
<i>Michelle G...</i>	8/25/04

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FOREIGN PATENT DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Publication Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Translation (If Appropriate)</u>
<u>jm</u>	EP 0588087	03/23/94	Ogawa et al. *	H01L	21/027	
	EP 0905565	03/31/99	Lu et al. *	G03F	7/09	
	EP 0987600	03/22/00	Adams et al. *	G03F	7/09	
	EP 0989460	03/29/00	Shimomura et al.	G03F	7/004	
	EP 1035442	09/13/00	Pavelchek et al. *	G03F	7/09	
	EP 1046958	10/25/00	Pawlowski et al. *	G03F	7/11	
	GB 2349148	10/25/00	Jung et al.	C07C	69/54	
	JP 10048831	02/20/98	Sony Corp.	G03F	007/11	Abstract
	JP 10048832	02/20/98	Sony Corp.	G03F	007/11	Abstract
	WO 0046643	08/10/00	Smith et al. *	G03F	9/00	
<u>nm</u>	WO 0054105	09/14/00	Foster et al.	G03C	1/492	

2/17/04

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Nick Hansen 8/25/04

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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

MB * G. Amblard et al., "Diffusion Phenomenon and Loss of Adhesion in Chemically Amplified Negative Resists", *Microelectronic Engineering*, 17, pp. 275-278 (1992).

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K. Kemp et al., "Effects of DUV Resist Sensitivities on Lithographic Process Window", *SPIE*, Vol. 3049, pp. 955-962 (1997).

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✓ * C. P. Soo et al., "Enhancement or Reduction of Catalytic Dissolution Reaction in Chemically Amplified Resists by Substrate Contaminants", *IEEE Transactions on Semiconductor Manufacturing*, Vol. 12, No. 4, pp. 462-469 (Nov 1999).

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